EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|----------|-------|--|--|---------------------|---------|------------------|
| L9 | 14887 | (epi\$6 or epita\$6) same (insulat\$6 or isolat\$6 or SiO2 or SiO?sub\$3 or ((Si or silicon) adj (oxide or dioxide))) same (thermal or heat\$6 or oxidat\$6 or anneal\$6 or RTA or RTP or temperature) same (interface or distort\$6 or nucle\$6 or lattice or oxygen or O2 or O?sub\$3 or oxidiz\$6 or semiconductor or substrate or wafer) | US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/01/03 13:32 |
| L10 | 9636 | 9 and (@ad<"20001116" or @rlad<"20001116") | US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/01/03 13:31 |
| L11 | 8238 | 10 and semiconductor | US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/01/03 13:31 |
| L12 . | 4152 | 11 and ((epi\$6 or epita\$6) near20 (insulat\$6 or isolat\$6 or SiO2 or SiO?sub\$3 or ((Si or silicon) adj (oxide or dioxide))) near20 (semiconductor or substrate or wafer or interface or distort\$6 or nucle\$6 or lattice or impurity or oxygen)) | US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/01/03 13:35 |
| L13 | 1978 | 12 and ((oxidiz\$6 or oxygen or O2 or O?sub\$3) same (heat\$6 or anneal\$6 or thermal or oxidat\$6 or RTA or RTP or temperature)) | US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB | OR | ON | 2007/01/03 13:36 |

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